

Introduction to CMOS VLSI Design

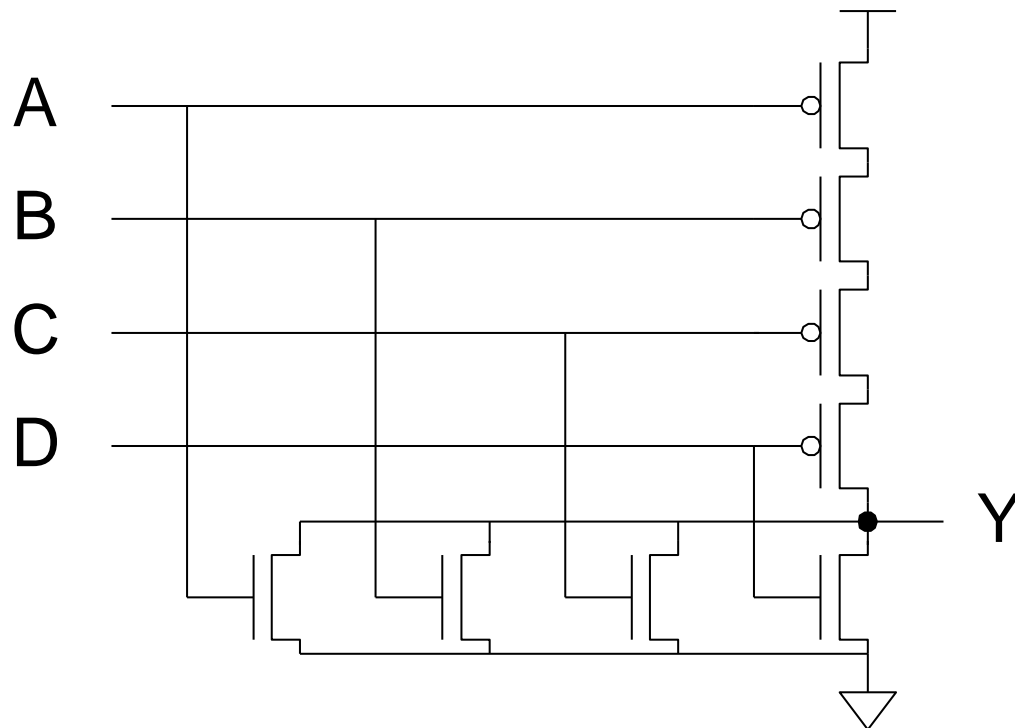
Lecture 5: Circuits & Layout

CMOS Gate Design

- Activity:
 - Sketch a 4-input CMOS NAND gate

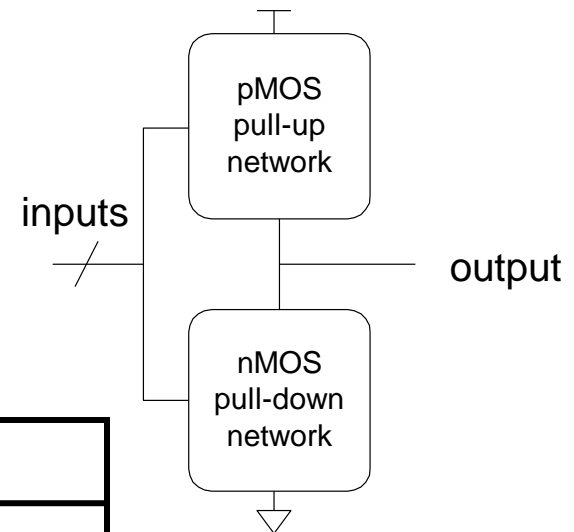
CMOS Gate Design

- Activity:
 - Sketch a 4-input CMOS NOR gate



Complementary CMOS

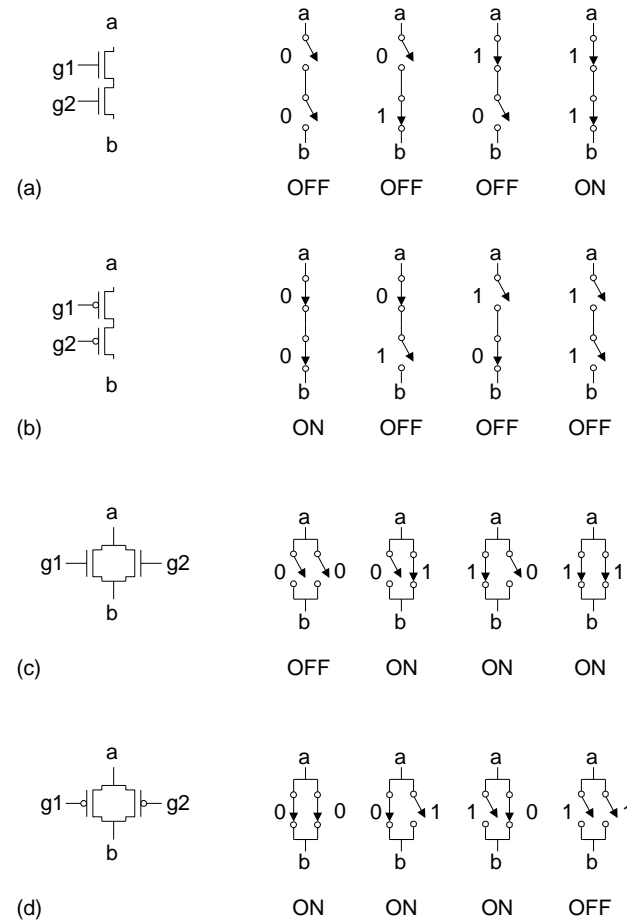
- ❑ Complementary CMOS logic gates
 - nMOS *pull-down network*
 - pMOS *pull-up network*
 - a.k.a. static CMOS



	Pull-up OFF	Pull-up ON
Pull-down OFF	Z (float)	1
Pull-down ON	0	X (crowbar)

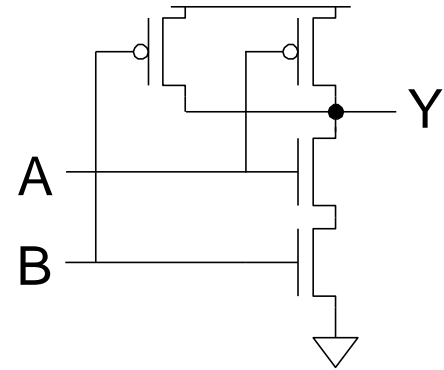
Series and Parallel

- ❑ nMOS: 1 = ON
- ❑ pMOS: 0 = ON
- ❑ *Series*: both must be ON
- ❑ *Parallel*: either can be ON



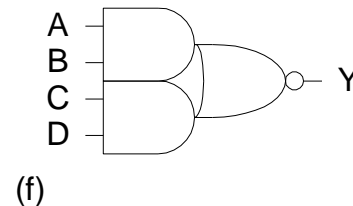
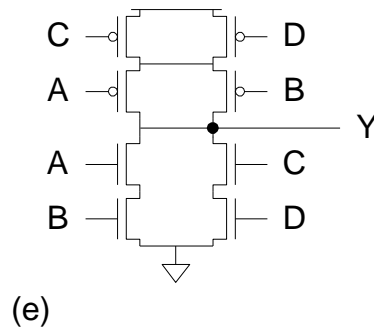
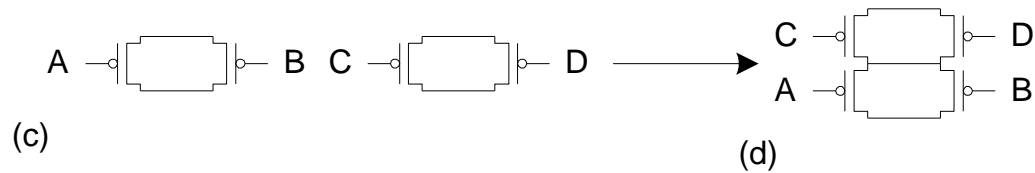
Conduction Complement

- ❑ Complementary CMOS gates always produce 0 or 1
- ❑ Ex: NAND gate
 - Series nMOS: $Y=0$ when both inputs are 1
 - Thus $Y=1$ when either input is 0
 - Requires parallel pMOS
- ❑ Rule of *Conduction Complements*
 - Pull-up network is complement of pull-down
 - Parallel \rightarrow series, series \rightarrow parallel



Compound Gates

- ❑ *Compound gates can do any inverting function*
- ❑ Ex: $Y = \overline{A \square B + C \square D}$ (AND-AND-OR-INVERT, AOI22)

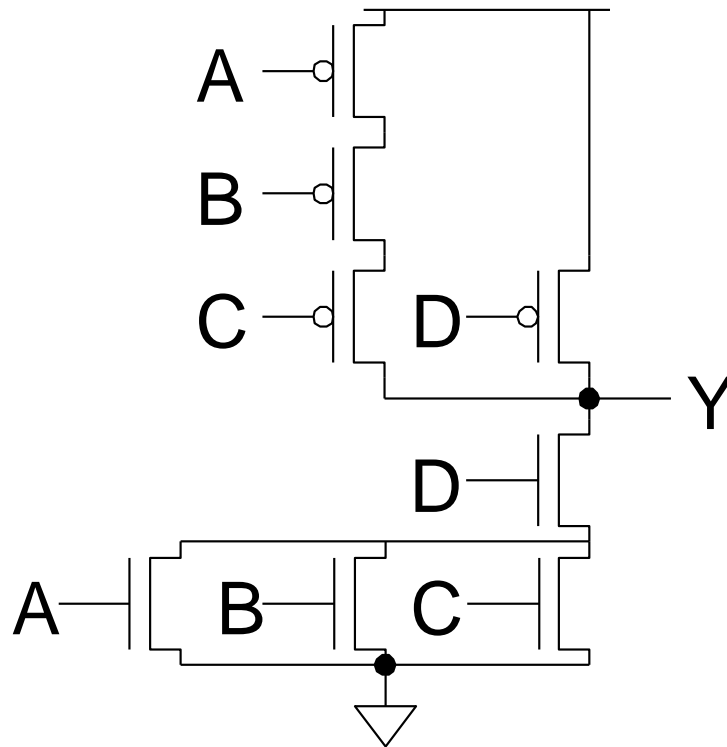


Example: O3AI

$$\square Y = \overline{(A + B + C)} \square D$$

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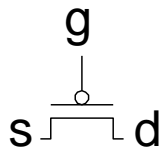
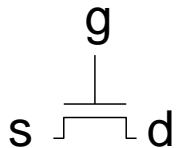


Signal Strength

- ❑ *Strength* of signal
 - How close it approximates ideal voltage source
- ❑ V_{DD} and GND rails are strongest 1 and 0
- ❑ nMOS pass strong 0
 - But degraded or weak 1
- ❑ pMOS pass strong 1
 - But degraded or weak 0
- ❑ Thus nMOS are best for pull-down network

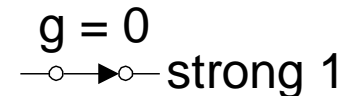
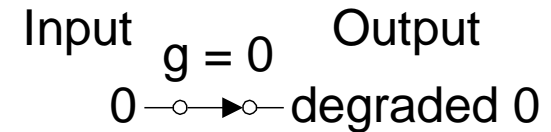
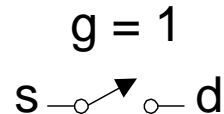
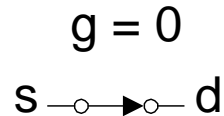
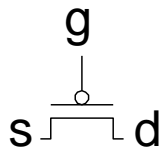
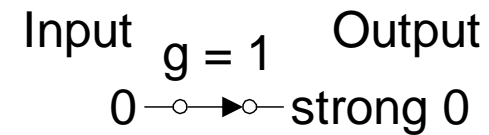
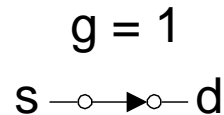
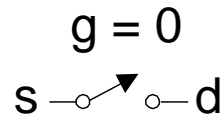
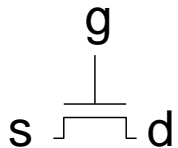
Pass Transistors

- ❑ Transistors can be used as switches



Pass Transistors

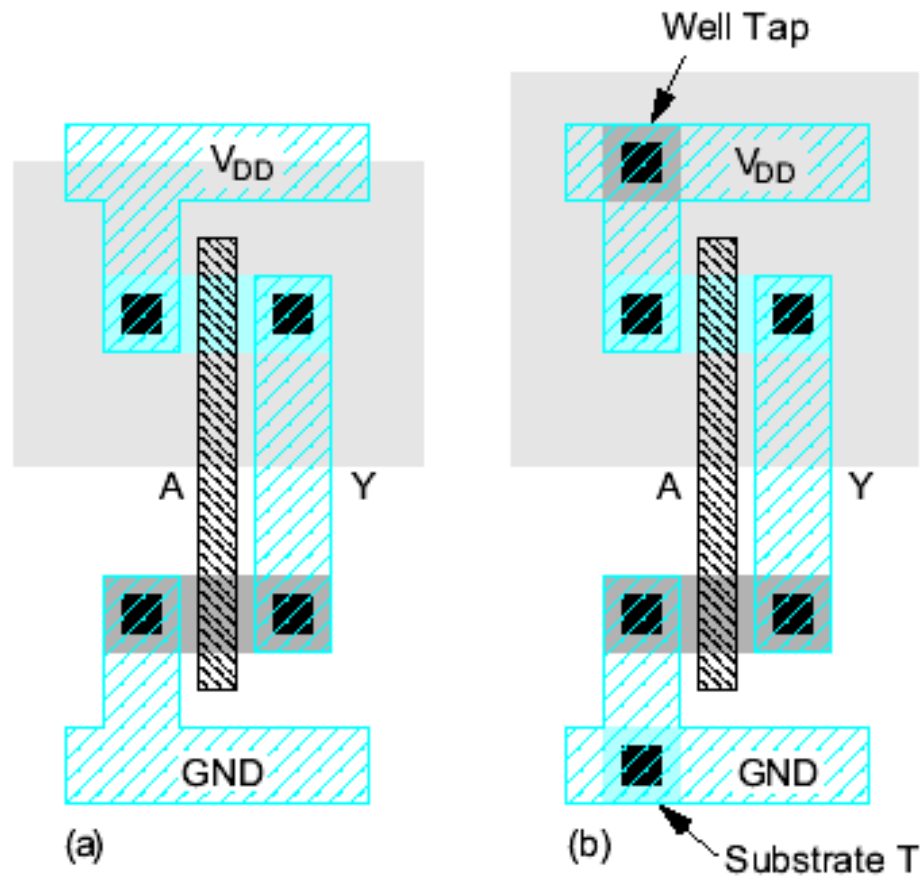
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Gate Layout

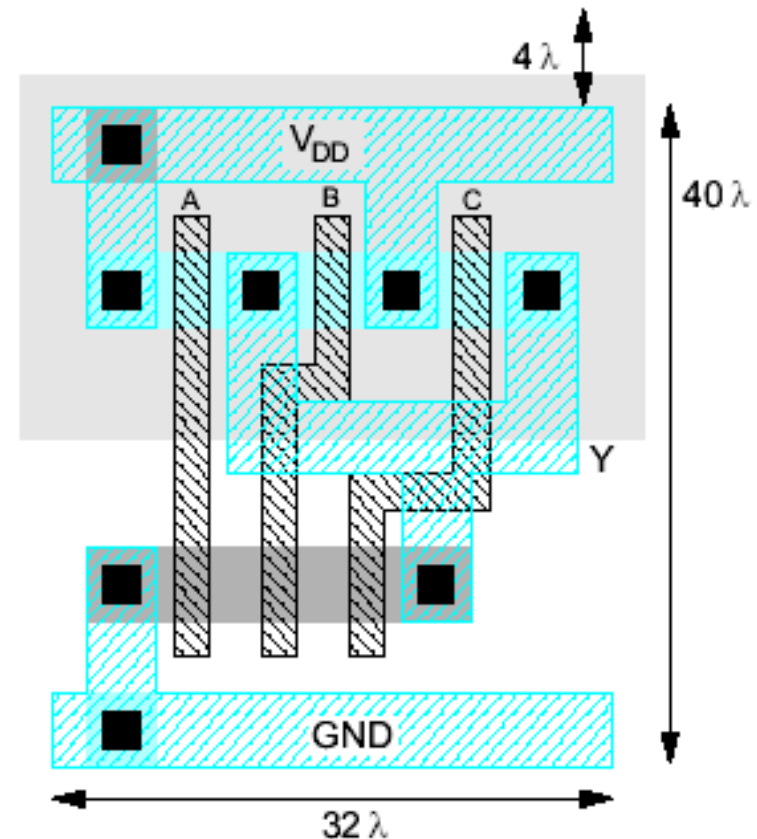
- ❑ Layout can be very time consuming
 - Design gates to fit together nicely
 - Build a library of standard cells
- ❑ Standard cell design methodology
 - V_{DD} and GND should abut (standard height)
 - Adjacent gates should satisfy design rules
 - nMOS at bottom and pMOS at top
 - All gates include well and substrate contacts

Example: Inverter



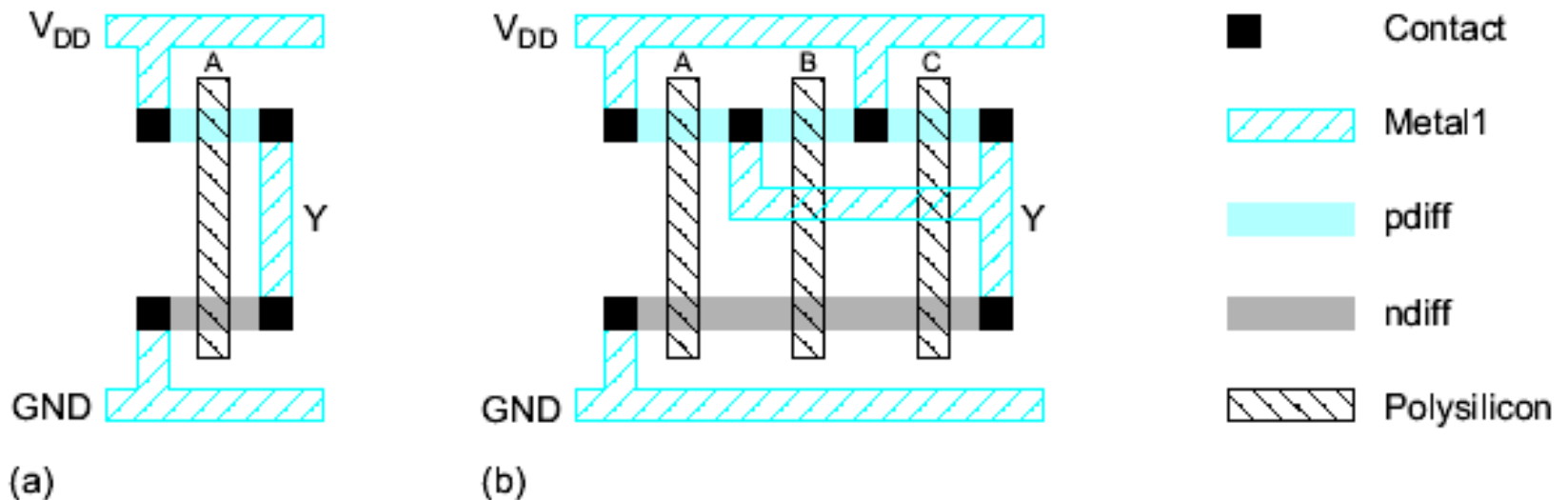
Example: NAND3

- ❑ Horizontal N-diffusion and p-diffusion strips
- ❑ Vertical polysilicon gates
- ❑ Metal1 V_{DD} rail at top
- ❑ Metal1 GND rail at bottom
- ❑ 32λ by 40λ



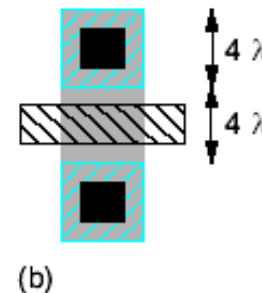
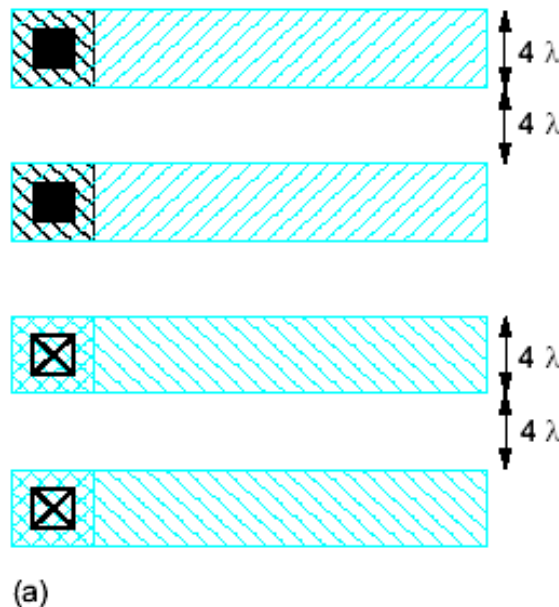
Stick Diagrams

- ❑ *Stick diagrams* help plan layout quickly
 - Need not be to scale
 - Draw with color pencils or dry-erase markers



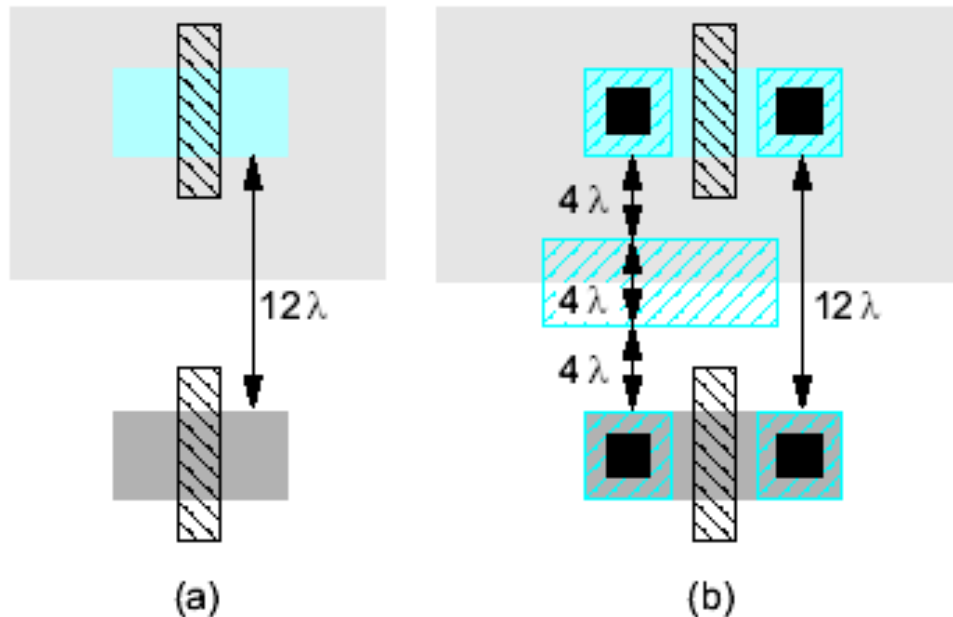
Wiring Tracks

- ❑ A *wiring track* is the space required for a wire
 - 4λ width, 4λ spacing from neighbor = 8λ pitch
- ❑ Transistors also consume one wiring track



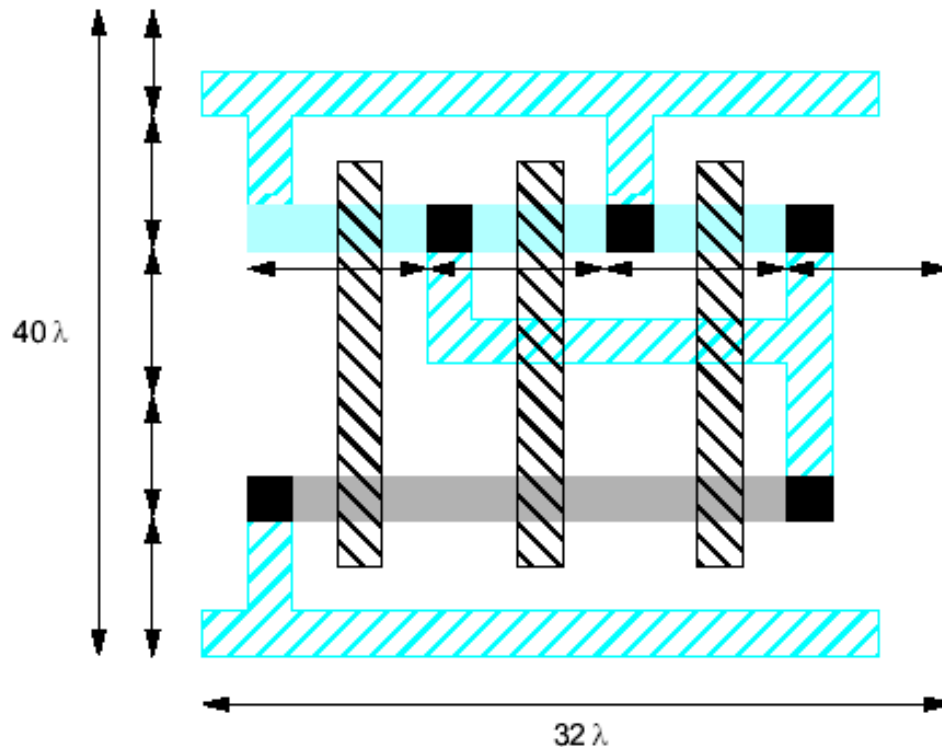
Well spacing

- ❑ Wells must surround transistors by 6λ
 - Implies 12λ between opposite transistor flavors
 - Leaves room for one wire track



Area Estimation

- ❑ Estimate area by counting wiring tracks
 - Multiply by 8 to express in λ



Example: O3AI

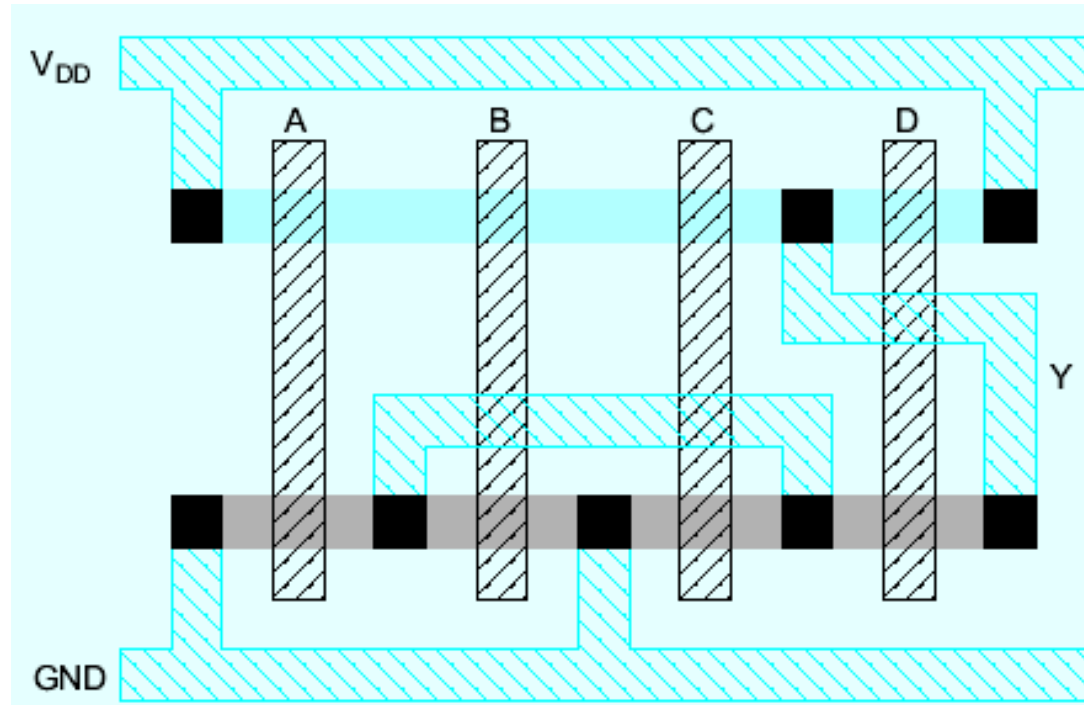
- Sketch a stick diagram for O3AI and estimate area

- $Y = \overline{(A + B + C)} \square D$

Example: O3AI

- Sketch a stick diagram for O3AI and estimate area

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